



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): **Annapragada et al.**

Group Art Unit: **2813**

Application Serial No.: **10/712,326**

Examiner: **Nguyen, Thanh T**

Filed: **November 12, 2003**

Title: **Minimizing the Loss of Barrier  
Materials During Photoresist  
Stripping**

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir/Madam:

This Amendment and Response is submitted in response to the Office Action dated May 16, 2005 in the above referenced patent application. A one-month extension is filed herewith. Please enter and consider the following amendments and remarks.

**Amendments to the Claims** are reflected in the listing of claims which begins on Page 2 of this paper.

**Remarks** begin on page 8.